

SYSTEM AND METHOD FOR DETERMINING STRAY LIGHT IN A THERMAL PROCESSING SYSTEM

Abstract

A system and method for determining the stray radiation within a heating chamber (74) of a thermal processing apparatus (22). The stray radiation is determined by moving a generally unheated wafer vertically through the heating chamber, and measuring with a detector (36) the amount of radiation reflected from the wafer at each vertical wafer position. The total measured radiation is then correlated with the stray radiation component of the total radiation.

Fig. 1